L Number	Hits	Search Text	DB	Time stamp
6	39224		USPAT;	2004/09/20 08:59
		and (photoresit or photosensitive) and	US-PGPUB;	
		<pre>(coat\$4 or layer\$4) and (exposur\$4 or radiat\$4 or irradiat\$4)</pre>	EPO; JPO; DERWENT	
7	19889	((substrate\$1 or wafer\$1 or workpiece\$1)	USPAT;	2004/09/20 08:55
		and (photoresit or photosensitive) and	US-PGPUB;	
		(coat\$4 or layer\$4) and (exposur\$4 or	EPO; JPO;	
		radiat\$4 or irradiat\$4)) and ((substrate\$1	DERWENT	
:		or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same		
		(coat\$4 or layer\$4)) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)		
8	9647	(((substrate\$1 or wafer\$1 or workpiece\$1)	USPAT;	2004/09/20 08:56
		and (photoresit or photosensitive) and	US-PGPUB; EPO; JPO;	
		<pre>(coat\$4 or layer\$4) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((substrate\$1</pre>	DERWENT	
j ,		or wafer\$1 or workpiece\$1) same	DEIE	
		(photoresit or photosensitive) same		
		(coat\$4 or layer\$4)) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) and ((substrate\$1		
		or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same		
		(coat\$4 or layer\$4) same (mask\$4 or		
		pattern\$4)) and (exposur\$4 or radiat\$4 or		
_		irradiat\$4)	rianam.	2004/00/20 00:56
9	1764	<pre>(((((substrate\$1 or wafer\$1 or workpiece\$1) and (photoresit or photosensitive) and</pre>	USPAT; US-PGPUB;	2004/09/20 08:56
		(coat\$4 or layer\$4) and (exposur\$4 or	EPO; JPO;	
		radiat\$4 or irradiat\$4)) and ((substrate\$1	DERWENT	
		or wafer\$1 or workpiece\$1) same		
		(photoresit or photosensitive) same		
		(coat\$4 or layer\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((substrate\$1		
		or wafer\$1 or workpiece\$1) same		
		(photoresit or photosensitive) same		
		(coat\$4 or layer\$4) same (mask\$4 or		•
		<pre>pattern\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((photoresit or</pre>		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4) same (ink\$1 or		
		liquid\$1 or fluid\$1) ) and (exposur\$4 or		
	000	radiat\$4 or irradiat\$4)	HCDAT.	2004/09/20 08:58
10	203	<pre>(((((substrate\$1 or wafer\$1 or workpiece\$1) and (photoresit or</pre>	USPAT; US-PGPUB;	2004/09/20 00.30
		photosensitive) and (coat\$4 or layer\$4)	EPO; JPO;	
		and (exposur\$4 or radiat\$4 or irradiat\$4))	DERWENT	
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4))		
		and (exposur\$4 or radiat\$4 or irradiat\$4))		
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4)) and (exposur\$4		
		or radiat\$4 or irradiat\$4)) and (exposure		
		((photoresit or photosensitive) same		
		(coat\$4 or layer\$4) same (mask\$4 or		
		pattern\$4) same (ink\$1 or liquid\$1 or fluid\$1) ) and (exposur\$4 or radiat\$4 or	1	
		irradiat\$4)) and ((photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4) same ((ink\$1 or		
		liquid\$1 or fluid\$1) with (jet\$4 or		
		eject\$4 or spray\$4))) and (exposur\$4 or radiat\$4 or irradiat\$4)		
L	L	Tagrachi or trragrachi	<del></del>	<u> </u>

		1	I 000 / /00 /00 00 00 00 00 00 00 00 00 0
11 11		USPAT;	2004/09/20 09:07
į l	workpiece\$1) and (photoresit or	US-PGPUB;	
	photosensitive) and (coat\$4 or layer\$4)	EPO; JPO;	
	and (exposur\$4 or radiat\$4 or irradiat\$4))	DERWENT	
	and ((substrate\$1 or wafer\$1 or		
	workpiece\$1) same (photoresit or		ļ
	<pre>photosensitive) same (coat\$4 or layer\$4))</pre>		į.
1	and (exposur\$4 or radiat\$4 or irradiat\$4))		İ
	and ((substrate\$1 or wafer\$1 or		
	workpiece\$1) same (photoresit or		
	photosensitive) same (coat\$4 or layer\$4)		
	same (mask\$4 or pattern\$4)) and (exposur\$4		
	or radiat\$4 or irradiat\$4)) and		
	((photoresit or photosensitive) same		
l i	(coat\$4 or layer\$4) same (mask\$4 or		
	pattern\$4) same (ink\$1 or liquid\$1 or		
	fluid\$1) ) and (exposur\$4 or radiat\$4 or		
	irradiat\$4)) and ((photoresit or		
	photosensitive) same (coat\$4 or layer\$4)		
	same (mask\$4 or pattern\$4) same ((ink\$1 or		
	liquid\$1 or fluid\$1) with (jet\$4 or		
	eject\$4 or spray\$4))) and (exposur\$4 or		
	radiat\$4 or irradiat\$4)) and ((photoresit		
	or photosensitive) same (coat\$4 or		ļ
	layer\$4) same ((mask\$4 or pattern\$4) with		
	(ink\$1 or liquid\$1 or fluid\$1) with (jet\$4		
	or eject\$4 or spray\$4))) and (exposur\$4 or		
	radiat\$4 or irradiat\$4)		
13	8   (((((((substrate\$1 or wafer\$1 or	USPAT;	2004/09/20 09:00
	workpiece\$1) and (photoresit or	US-PGPUB;	
1	photosensitive) and (coat\$4 or layer\$4)	EPO; JPO;	
	and (exposur\$4 or radiat\$4 or irradiat\$4))	DERWENT	
	and ((substrate\$1 or wafer\$1 or		
	workpiece\$1) same (photoresit or		
	photosensitive) same (coat\$4 or layer\$4))		
	and (exposur\$4 or radiat\$4 or irradiat\$4))		
	and ((substrate\$1 or wafer\$1 or		
•	workpiece\$1) same (photoresit or		
	photosensitive) same (coat\$4 or layer\$4)		
	same (mask\$4 or pattern\$4)) and (exposur\$4		
	or radiat\$4 or irradiat\$4)) and		
1	((photoresit or photosensitive) same		
	(coat\$4 or layer\$4) same (mask\$4 or		
ĺ	pattern\$4) same (ink\$1 or liquid\$1 or		
	fluid\$1) ) and (exposur\$4 or radiat\$4 or		
	irradiat\$4)) and ((photoresit or		
	photosensitive) same (coat\$4 or layer\$4)		
	same (mask\$4 or pattern\$4) same ((ink\$1 or		
	liquid\$1 or fluid\$1) with (jet\$4 or		
	eject\$4 or spray\$4))) and (exposur\$4 or		
	radiat\$4 or irradiat\$4)) and ((photoresit		
	or photosensitive) same (coat\$4 or		
	layer\$4) same ((mask\$4 or pattern\$4) with	]	
	(ink\$1 or liquid\$1 or fluid\$1) with (jet\$4		
	or eject\$4 or spray\$4))) and (exposur\$4 or		
	radiat\$4 or irradiat\$4)) and ((photoresit		
	or photosensitive) same (coat\$4 or		
1	layer\$4) same ((mask\$4 or pattern\$4) with		
1	layer\$4) same ((mask\$4 or pattern\$4) with (ink\$1 or liquid\$1 or fluid\$1) with (jet\$4		
	layer\$4) same ((mask\$4 or pattern\$4) with (ink\$1 or liquid\$1 or fluid\$1) with (jet\$4 or eject\$4 or spray\$4)) same (exposur\$4 or		
	layer\$4) same ((mask\$4 or pattern\$4) with (ink\$1 or liquid\$1 or fluid\$1) with (jet\$4 or eject\$4 or spray\$4)) same (exposur\$4 or radiat\$4 or irradiat\$4))) and		
	layer\$4) same ((mask\$4 or pattern\$4) with (ink\$1 or liquid\$1 or fluid\$1) with (jet\$4 or eject\$4 or spray\$4)) same (exposur\$4 or		

77 (((((((((substrate\$1 or wafer\$1 or workpiece\$1) and (photoresit or photosensitive) and (coat\$4 or layer\$4) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4)) and (exposur\$4 or radiat\$4) and ((photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4) and (exposur\$4 or radiat\$4)) and (fint or liquid\$1 or fluid\$1)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and (photoresit or photosensitive) same (radiat\$4)) and (photoresit or photosensitive) same (radiat\$4)) and (photoresit or radiat\$4) and (photoresit or radiat\$4)) and (photoresit or radiat\$4)) and (photoresit or radiat\$4)	
photosensitive) and (coat\$4 or layer\$4) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4) same (ink\$1 or liquid\$1 or fluid\$1) ) and (exposur\$4 or radiat\$4 or	2
and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4) same (ink\$1 or liquid\$1 or fluid\$1) ) and (exposur\$4 or radiat\$4 or	
and ((substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((photoresit or photosensitive) same (coat\$4 or layer\$4) same (foat\$4 or layer\$4) same (foat\$4 or layer\$4) and (foat\$4 or layer\$4) same (mask\$4 or pattern\$4) same (mask\$4 or layer\$4) same (mask\$4 or pattern\$4) same (ink\$1 or liquid\$1 or fluid\$1)) and (exposur\$4 or radiat\$4 or	
<pre>workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4) same (ink\$1 or liquid\$1 or fluid\$1) ) and (exposur\$4 or radiat\$4 or</pre>	
photosensitive) same (coat\$4 or layer\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4) same (ink\$1 or liquid\$1 or fluid\$1) ) and (exposur\$4 or radiat\$4 or	
and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4) same (ink\$1 or liquid\$1 or fluid\$1) ) and (exposur\$4 or radiat\$4 or	
and ((substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4) same (ink\$1 or liquid\$1 or fluid\$1) and (exposur\$4 or radiat\$4 or	
<pre>workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and   ((photoresit or photosensitive) same   (coat\$4 or layer\$4) same (mask\$4 or   pattern\$4) same (ink\$1 or liquid\$1 or   fluid\$1) ) and (exposur\$4 or radiat\$4 or</pre>	
photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4) same (ink\$1 or liquid\$1 or fluid\$1) ) and (exposur\$4 or radiat\$4 or	
same (mask\$4 or pattern\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4) same (ink\$1 or liquid\$1 or fluid\$1)) and (exposur\$4 or radiat\$4 or	
or radiat\$4 or irradiat\$4)) and ((photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4) same (ink\$1 or liquid\$1 or fluid\$1) ) and (exposur\$4 or radiat\$4 or	
((photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4) same (ink\$1 or liquid\$1 or fluid\$1) ) and (exposur\$4 or radiat\$4 or	
(coat\$4 or layer\$4) same (mask\$4 or pattern\$4) same (ink\$1 or liquid\$1 or fluid\$1) ) and (exposur\$4 or radiat\$4 or	
pattern\$4) same (ink\$1 or liquid\$1 or fluid\$1) ) and (exposur\$4 or radiat\$4 or	
fluid\$1) ) and (exposur\$4 or radiat\$4 or	
irradiatSALL and ((photoresit or	
photosensitive) same (coat\$4 or layer\$4)	
same (mask\$4 or pattern\$4) same ((ink\$1 or	
liquid\$1 or fluid\$1) with (jet\$4 or	
eject\$4 or spray\$4))) and (exposur\$4 or	,
radiat\$4 or irradiat\$4)) and ((photoresit	
or photosensitive) same (coat\$4 or	
layer\$4) same ((mask\$4 or pattern\$4) with	
(ink\$1 or liquid\$1 or fluid\$1) with (jet\$4	
or eject\$4 or spray\$4))) and (exposur\$4 or	
radiat\$4 or irradiat\$4)) and ((photoresit	
or photosensitive) same (coat\$4 or	
layer\$4) same ((mask\$4 or pattern\$4) with	
(ink\$1 or liquid\$1 or fluid\$1) with (jet\$4	
or eject\$4 or spray\$4)) same (exposur\$4 or	
radiat\$4 or irradiat\$4))	

	40	[ / / / / / / / / / / / / / / / / / / /	TICDAM.	2004/09/20 09:12
14	42	((((((substrate\$1 or wafer\$1 or	USPAT;	2004/09/20 09:12
		workpiece\$1) and (photoresit or	US-PGPUB;	
		photosensitive) and (coat\$4 or layer\$4)	EPO; JPO;	
		and (exposur\$4 or radiat\$4 or irradiat\$4))	DERWENT	
		and ((substrate\$1 or wafer\$1 or		
	1	workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4))		
		and (exposur\$4 or radiat\$4 or irradiat\$4))		
	!	and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4)) and (exposur\$4		
		or radiat\$4 or irradiat\$4)) and		
		((photoresit or photosensitive) same		
		(coat\$4 or layer\$4) same (mask\$4 or		
		pattern\$4) same (ink\$1 or liquid\$1 or		
		fluid\$1) ) and (exposur\$4 or radiat\$4 or		
		irradiat\$4)) and ((photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4) same ((ink\$1 or		•
	İ	liquid\$1 or fluid\$1) with (jet\$4 or		
		eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) and ((photoresit		
		or photosensitive) same (coat\$4 or		
		layer\$4) same ((mask\$4 or pattern\$4) with		
		(ink\$1 or liquid\$1 or fluid\$1) with (jet\$4		
		or eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) not		
		((((((((substrate\$1 or wafer\$1 or		
		workpiece\$1) and (photoresit or		
	i	photosensitive) and (coat\$4 or layer\$4)		
		and (exposur\$4 or radiat\$4 or irradiat\$4))		
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or	1	
		photosensitive) same (coat\$4 or layer\$4))		
		and (exposur\$4 or radiat\$4 or irradiat\$4))		
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4)) and (exposur\$4		
		or radiat\$4 or irradiat\$4)) and		
		((photoresit or photosensitive) same		
		(coat\$4 or layer\$4) same (mask\$4 or		
		pattern\$4) same (ink\$1 or liquid\$1 or		
		fluid\$1) ) and (exposur\$4 or radiat\$4 or		
		irradiat\$4)) and ((photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4) same ((ink\$1 or		
ľ		liquid\$1 or fluid\$1) with (jet\$4 or		
		eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) and ((photoresit		
		or photosensitive) same (coat\$4 or		
		layer\$4) same ((mask\$4 or pattern\$4) with		
1		(ink\$1 or liquid\$1 or fluid\$1) with (jet\$4		
		or eject\$4 or spray\$4))) and (exposur\$4 or		
	1	radiat\$4 or irradiat\$4)) and ((photoresit		
		or photosensitive) same (coat\$4 or		
		layer\$4) same ((mask\$4 or pattern\$4) with		
		(ink\$1 or liquid\$1 or fluid\$1) with (jet\$4		
[		or eject\$4 or spray\$4)) same (exposur\$4 or		
		radiat\$4 or irradiat\$4)))	<u></u>	
		radiat\$4 or irradiat\$4)))		

15	84	(((((substrate\$1 or wafer\$1 or	USPAT;	2004/09/20 09:12
== ="		workpiece\$1) and (photoresit or	US-PGPUB;	
		photosensitive) and (coat\$4 or layer\$4)	EPO; JPO;	
		and (exposur\$4 or radiat\$4 or irradiat\$4))	DERWENT	
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4))		
		and (exposur\$4 or radiat\$4 or irradiat\$4))		
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4)) and (exposur\$4		
		or radiat\$4 or irradiat\$4)) and		
		((photoresit or photosensitive) same		
		(coat\$4 or layer\$4) same (mask\$4 or		
		pattern\$4) same (ink\$1 or liquid\$1 or		
		fluid\$1) ) and (exposur\$4 or radiat\$4 or		
		irradiat\$4)) and ((photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4) same ((ink\$1 or		
		liquid\$1 or fluid\$1) with (jet\$4 or		i
		eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) not		
		(((((((substrate\$1 or wafer\$1 or		
		workpiece\$1) and (photoresit or		
		photosensitive) and (coat\$4 or layer\$4)		
		and (exposur\$4 or radiat\$4 or irradiat\$4))		
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4))		
		and (exposur\$4 or radiat\$4 or irradiat\$4))		
	İ	and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4)) and (exposur\$4		
		or radiat\$4 or irradiat\$4)) and		
		((photoresit or photosensitive) same		1
		(coat\$4 or layer\$4) same (mask\$4 or		
		pattern\$4) same (ink\$1 or liquid\$1 or		
		fluid\$1) ) and (exposur\$4 or radiat\$4 or		
		irradiat\$4)) and ((photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4) same ((ink\$1 or		
		liquid\$1 or fluid\$1) with (jet\$4 or		
		eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) and ((photoresit		
		or photosensitive) same (coat\$4 or		
		layer\$4) same ((mask\$4 or pattern\$4) with		
		(ink\$1 or liquid\$1 or fluid\$1) with (jet\$4		
		or eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4))		

Page 5

		<u>'</u>		
16	19	((((((substrate\$1 or wafer\$1 or	USPAT;	2004/09/20 09:15
		workpiece\$1) and (photoresit or	US-PGPUB;	
		photosensitive) and (coat\$4 or layer\$4)	EPO; JPO;	
,		<pre>and (exposur\$4 or radiat\$4 or irradiat\$4))</pre>	DERWENT	
		and ((substrate\$1 or wafer\$1 or		·
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4))		
İ		and (exposur\$4 or radiat\$4 or irradiat\$4))		
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4)) and (exposur\$4		
		or radiat\$4 or irradiat\$4)) and		
		((photoresit or photosensitive) same		
		(coat\$4 or layer\$4) same (mask\$4 or		
		pattern\$4) same (ink\$1 or liquid\$1 or		
		fluid\$1) ) and (exposur\$4 or radiat\$4 or		
		irradiat\$4)) and ((photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4) same ((ink\$1 or		
		liquid\$1 or fluid\$1) with (jet\$4 or		
		eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) not		
		((((((substrate\$1 or wafer\$1 or		
		workpiece\$1) and (photoresit or		
		photosensitive) and (coat\$4 or layer\$4)		
		and (exposur\$4 or radiat\$4 or irradiat\$4))		
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4))		
		and (exposur\$4 or radiat\$4 or irradiat\$4))		
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4)) and (exposur\$4		
		or radiat\$4 or irradiat\$4)) and		
		((photoresit or photosensitive) same		
		(coat\$4 or layer\$4) same (mask\$4 or		
		pattern\$4) same (ink\$1 or liquid\$1 or		
		fluid\$1) ) and (exposur\$4 or radiat\$4 or		
		irradiat\$4)) and ((photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4) same ((ink\$1 or		
		liquid\$1 or fluid\$1) with (jet\$4 or		
		eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) and ((photoresit		
1		or photosensitive) same (coat\$4 or		
		layer\$4) same ((mask\$4 or pattern\$4) with		
		(ink\$1 or liquid\$1 or fluid\$1) with (jet\$4		
		or eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4))) and (rotat\$4 or		
		circul\$4)		

		· · · · · · · · · · · · · · · · · · ·		
17	65	((((((substrate\$1 or wafer\$1 or	USPAT;	2004/09/20 09:16
		workpiece\$1) and (photoresit or	US-PGPUB;	
		photosensitive) and (coat\$4 or layer\$4)	EPO; JPO; DERWENT	
		and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((substrate\$1 or wafer\$1 or	DEVMENT	
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4))		
		and (exposur\$4 or radiat\$4 or irradiat\$4))		
		and ((substrate\$1 or wafer\$1 or	·	
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4)) and (exposur\$4		
		or radiat\$4 or irradiat\$4)) and		
		((photoresit or photosensitive) same		
		(coat\$4 or layer\$4) same (mask\$4 or		
		pattern\$4) same (ink\$1 or liquid\$1 or		
		fluid\$1) ) and (exposur\$4 or radiat\$4 or		
		irradiat\$4)) and ((photoresit or   photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4) same ((ink\$1 or		
		liquid\$1 or fluid\$1) with (jet\$4 or		
		eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) not		
		((((((substrate\$1 or wafer\$1 or		
		workpiece\$1) and (photoresit or		
		photosensitive) and (coat\$4 or layer\$4)		
		and (exposur\$4 or radiat\$4 or irradiat\$4))		
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4))		
		and (exposur\$4 or radiat\$4 or irradiat\$4))		
		and ((substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4)) and (exposur\$4		
		or radiat\$4 or irradiat\$4)) and		
		((photoresit or photosensitive) same		
		(coat\$4 or layer\$4) same (mask\$4 or		
		pattern\$4) same (ink\$1 or liquid\$1 or		
		fluid\$1) ) and (exposur\$4 or radiat\$4 or		
		irradiat\$4)) and ((photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4) same ((ink\$1 or		
		liquid\$1 or fluid\$1) with (jet\$4 or		
		eject\$4 or spray\$4))) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((photoresit		
		or photosensitive) same (coat\$4 or		
		layer\$4) same ((mask\$4 or pattern\$4) with		
		(ink\$1 or liquid\$1 or fluid\$1) with (jet\$4		1
		or eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4))) not		
		(((((((substrate\$1 or wafer\$1 or		
		workpiece\$1) and (photoresit or		
		photosensitive) and (coat\$4 or layer\$4)		
		and (exposur\$4 or radiat\$4 or irradiat\$4))		
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		<pre>photosensitive) same (coat\$4 or layer\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4))</pre>		
		and (exposurs4 or radiats4 or irradiats4)) and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4)) and (exposur\$4		
		or radiat\$4 or irradiat\$4)) and	1	
		((photoresit or photosensitive) same	1	
		(coat\$4 or layer\$4) same (mask\$4 or		
		pattern\$4) same (ink\$1 or liquid\$1 or	1	
		fluid\$1) ) and (exposur\$4 or radiat\$4 or		
		irradiat\$4)) and ((photoresit or	1	
		photosensitive) same (coat\$4 or layer\$4)		
1		same (mask\$4 or pattern\$4) same ((ink\$1 or liquid\$1 or fluid\$1) with (jet\$4 or		
Search His	tory 9	/siect\$4 or apray\$4)), and (exposur\$4 or radiat\$4 or ifradiat\$4) not		
		(((((((substrate\$1 or wafer\$1 or		
		workpiece\$1) and (photoresit or		
1	I	the commence of the contract o	I	I